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Form PTO-1449		U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE		ATTY. DOCKET NO. MI22-2297		SERIAL NO. Filed Herewith	
LIST OF ART CITED BY APPLICANT (Use several sheets if necessary)				APPLICANT Garo J. Derderian et al.			
				FILING DATE Filed Herewith		GROUP Unknown	
U.S. PATENT DOCUMENTS							
*Examiner Initial		Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate
MWS	AA	6,444,495 B1	09/02	Leung et al.			
OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)							
MWS	AB	Frank, M. et al., "Enhanced Initial Growth of Atomic-Layer-Deposited Metal Oxides on Hydrogen-Terminated Silicon", App. Phys. Lett., Vol. 83, No. 4, July 28, 2003, pp. 740-742.					
MWS	AC	Rosidian, A. et al., "Formation of Ultrahard Metal Oxide Nanocluster Coatings at Room Temperature by Electrostatic Self-Assembly", SPIE Vol. 3675 (1999), pp. 113-119.					
MWS	AD	Sakaue, H. et al., "Conformable CVD of SiO <sub>2</sub> into Deep Trench Using the Digital Method", Extended Abstracts of the 22nd (1990 International) Conf. on Solid State Devices and Materials, Sendai (1990), pp. 921-924.					
MWS	AE	Mountziaris, T. et al., "Gas-Phase and Surface Chemistry in Electronic Materials Processing", Materials Research Society Symposium Proceedings, Vol. 334, held 11/29/93 - 12/2/93, Boston, MA, pp. 1-36.					
MWS	AF	Perez, I. et al., "Fabrication and Characterization of 4H-SiC MOS Capacitors with Atomic Layer Deposited (ALD) SiO <sub>2</sub> ", IEEE 7/00, pp. 144-147.					
MWS	AG	Sakaue, H. et al., "Digital Chemical Vapor Deposition of SiO <sub>2</sub> Using a Repetitive Reaction of Triethylsilane/Hydrogen and Oxidation", JP Journal of App. Phys., Vol. 70, No. 1B, Jan. 1991, pp. L 124-L 127.					
MWS	AH	Klaus, J. et al., "Atomic Layer Deposition of SiO <sub>2</sub> at Room Temperature Using NH <sub>3</sub> -Catalyzed Sequential Surface Reactions", Surface Science 447 (2000), pp. 81-90.					
MWS	AI	Cameron, M. et al., "Atomic Layer Deposition of SiO <sub>2</sub> and TiO <sub>2</sub> in Alumina Tubular Membranes: Pore Reduction and Effect of Surface Species on Gas Transport", Langmuir 2000, 16, pp. 7435-7444.					
MWS	AJ	Horiike, Y. et al., "Filling of Si Oxide into a Deep Trench Using Digital CVD Method", App. Surface Science 46, (1990), pp. 168-174.					
MWS	AK	Wise, M. et al., "Diethyldiethoxysilane as a New Precursor for SiO <sub>2</sub> Growth on Silicon", Mat. Res. Soc. Symp. Proc. Vol. 334, (©1994 Materials Research Society), pp. 37-43.					
EXAMINER /Matthew Such/				DATE CONSIDERED 11/15/2006			
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LIST OF ART CITED BY APPLICANT (Use several sheets if necessary)				APPLICANT Garo J. Derderian et al.			
				FILING DATE Filed Herewith	GROUP Unknown		
U.S. PATENT DOCUMENTS							
*Examiner Initial		Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate
MWS	AA	US2003/ 0026989 A1	Pub. 2/6/03	George et al.			07/16/02
MWS	AB	US2002/ 0137260 A1	Pub. 9/26/02	Leung et al.			01/11/01
	AC						
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	AI						
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FOREIGN PATENT DOCUMENTS							
		Document Number	Date	Country	Class	Subclass	Translation
							Yes    No
	AM						
	AN						
	AO						
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OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)							
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EXAMINER        /Matthew Such/				DATE CONSIDERED        11/15/2006			
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Form PTO-1449 U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE				ATTY. DOCKET NO. M22-2297		SERIAL NO. 10728,328	
LIST OF ART CITED BY APPLICANT (Use separate sheets if necessary)				APPLICANT: Gary J. Dardarian et al.			
				FILING DATE: December 1, 2003		GROUP: Unknown	
U.S. PATENT DOCUMENTS							
Examiner Initial		Document Number	Date	Name	Class	Subclass	Filing Date if Appropriate
	AA						
	AB						
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FOREIGN PATENT DOCUMENTS							
		Document Number	Date	Country	Class	Subclass	Translation
							Yes No
	AM						
	AN						
	AO						
	AP						
	AQ						
OTHER REFERENCES (Including Author, Title, Date, Pertinent Pages, Etc.)							
MWS	AR	Klaus, J.W. et al., "Atomic Layer Deposition of SiO <sub>2</sub> Using Catalyzed and Uncatalyzed Self-Limiting Surface Reactions",					
		Surface Review and Letters, Vol. 6, Nos. 3 & 4 (1999), © World Scientific Pub. Co., pp. 435-448.					
	AS						
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